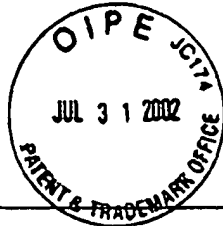


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(PTO-1449)

ATTY. DOCKET NO.
6301/Consilium/DV

SERIAL NO.
09/928,474

APPLICANT
Badri N. KRISHNAMURTHY et al.

FILING DATE
August 14, 2001

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AS	 	 	 	 	 	

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<i>AS</i>	5,220,517	06/15/93	Sierk et al.			08/31/90
	5,329,463	07/12/94	Sierk et al.			01/13/93
	5,495,417	02/27/96	Fuduka et al.			03/16/93
	5,497,316	03/05/96	Sierk et al.			04/04/95
	5,503,707	04/02/96	Maung et al.			09/22/93
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<i>AS</i>	2,050,247	08/29/91	Canada			X	
	2,165,847	08/29/91	Canada			X	
	2,194,855	08/29/91	Canada			X	
	05-151231	06/18/93	Japan				X
	05-216896	08/27/93	Japan				X
	05-266029	10/15/93	Japan				X
	06-110894	04/22/94	Japan				X
	06-176994	06/24/94	Japan				X
	06-252236	09/09/94	Japan				X
	06-260380	09/16/94	Japan				X
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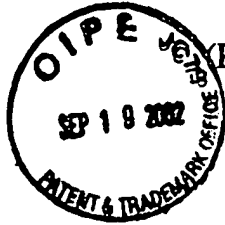
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OJ	5,859,964	01/12/99	Wang et al.			10/25/96
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	5,870,306	02/09/99	Harada			06/13/97
	5,903,455	05/11/99	Sharpe, Jr. et al.			12/12/96
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	5,963,881	10/05/99	Kahn et al.			10/20/97
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	6,041,270	03/21/00	Steffan et al.			12/05/97
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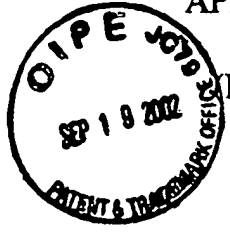
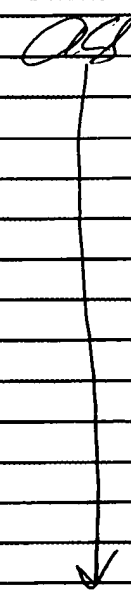
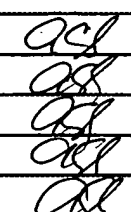

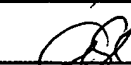

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OJ	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
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<i>Anda Stevens</i>	02-25-05

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(PTO-1449)				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2171	
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	4,698,766	10/06/87	Entwistle et al.			05/17/85	
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	5,226,118	07/06/93	Baker et al.			01/29/91	
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	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
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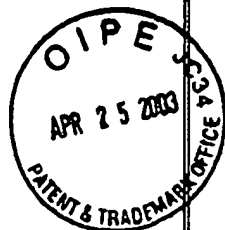
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**INFORMATION DISCLOSURE
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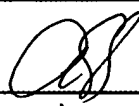
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Badri N. KRISHNAMURTHY et al.

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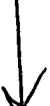
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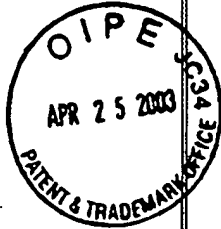
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	WO 01/25865	04/12/01	WIPO			X	
	434103	05/16/01	Taiwan			X	
	436383	05/28/01	Taiwan			X	
	455938	09/21/01	Taiwan			X	
	455976	09/21/01	Taiwan			X	
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OS	61-66104	04/04/86	Japan			X	
	3-202710	09/04/91	Japan			X	
	8-23166	01/23/96	Japan			X	
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↓	EP 1 067 757	01/10/01	Europe			X	
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 99/59200 ✓	11/18/99	WIPO			X	
	WO 01/52319 ✓	07/19/01	WIPO			X	
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	Williams, Randy, Dadi Gudmundsson, Kevin Monahan, Raman Nurani, Meryl Stoller and J. George Shanthikumar. October 1999. "Optimized Sample Planning for Wafer Defect Inspection," <i>Semiconductor Manufacturing Conference Proceedings, 1999 IEEE International Symposium on Santa Clara, CA</i> . Piscataway, NJ. pp. 43 - 46.						
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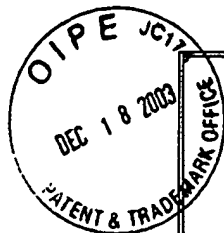
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SHEET 2 OF 2

<p align="center">INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</p>				ATTY. DOCKET NO. 006301 USA/Consilium/Consilium/ DK		SERIAL NO. 09/928,474	
				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2812	
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation Yes No	
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EXAMINER 				DATE CONSIDERED 02-25-05			

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SHEET 1 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)	ATTY. DOCKET NO. 006301 USA/Consilium/Consilium/ DK	SERIAL NO. 09/928,474
	APPLICANT Badri N. KRISHNAMURTHY et al.	
	FILING DATE August 14, 2001	GROUP 2812

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						Yes	No
CSA	WO 01/11679	02/15/01	WIPO			X	
	WO 01/080306	10/25/01	WIPO			X	

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(PTO-1449)



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APPLICANT
Badri N. KRISHNAMURTHY et al.

FILING DATE
August 14, 2001

GROUP
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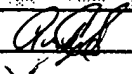

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02-25-05

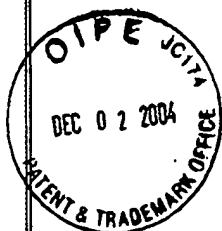
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	APPLICANT Badri N. KRISHNAMURTHY et al.	
	FILING DATE August 14, 2001	GROUP 2812
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(PTO-1449)



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APPLICANT
Badri N. KRISHNAMURTHY et al.

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						Yes	No
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(PTO-1449)

ATTY. DOCKET NO.
6301/Consilium/DV

SERIAL NO.
09/928,474

APPLICANT
Badri N. KRISHNAMURTHY, et al.

FILING DATE
August 14, 2001

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